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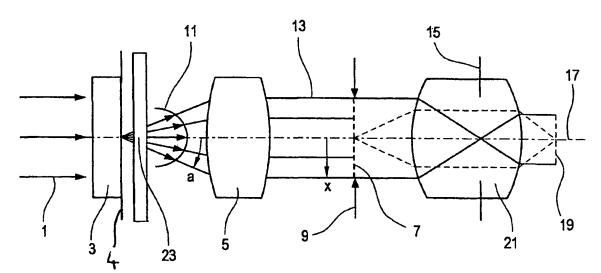
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#### (54) Title: AN ILLUMINATION SYSTEM FOR MICROLITHOGRAPHY



(57) Abstract: The present invention relates to an illumination system for microlithography, especially for wavelengths ≤ 193 nm, especially preferably for EUV lithography for illuminating a field in a field plane (9) with at least one optical integrator (3) which splits up a light bundle emitted by a light source into a plurality of light channels each having a light intensity, characterized in that a filter (23) is provided in the light path from the light source to the field plane (9), with the filter comprising filter elements which are configured in such a way that the light intensity of at least one light channel is reduced in the light path after the filter element.



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